

Microwave Device Reliability Characterization -The Mechanics of Life Test Execution and Analysis

Air

Land

Sea

Space

Cyberspace

Innovation. In all domains.

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Microwave Device Reliability Characterization -The Mechanics of Life Test Execution and Analysis

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Reliability Lab Charter

- Perform All Due Diligence Testing to Establish and Maintain the MMIC Fab Process Reliability to ensure 'NoDoubt' Mission Assurance
- Provide Reliability Expertise Within RFC, IDS and Company Wide
- Anticipate Test Capability and Capacity Needs to Enable Nimble Response to Programs' Needs
- Search for New Paradigms in Testing and Reliability Benchmarks Industry Wide
- Implement Lean Methods and Automation to Optimize Quantity and Enhance the Quality of Test Execution and Data Analysis



Reliability Lab Test Capabilities

- Life Testing:
 - Process Reliability Monitoring
 - DC Biased Temperature Accelerated Life Test
 - RF Operational Life Test (S & X-Band).....→
 - RF Temperature Accelerated Life Test (X-Band)
 - Pulsed DC Electromigration (DC TALT)
 - Current Density Testing (DC TALT)

- Characterization:
 - Capacitor Time Dependent Dielectric Breakdown Testing
 - LabVIEW Based Parametric Characterization
 - Resistor TCR Characterization
 - Light Emission Microscopy→
 - Liquid Crystal Failure Analysis



What Affects Reliability?

- Technical or lay, we all know that the reliability or longevity of “things” is driven by stress
- The list of life reducing stresses include: temperature, temperature cycling, humidity, voltage/electric field, current density, mechanical stress, thermo-mechanical stress cycling, radiation etc
- The dominating stresses depend on the application environment.
- Most of us would instinctively recognize Temperature as a common stress for many “things”.

Temperature is a common stress driver of reliability

The Focus of Today's Presentation

- Our “things” of interest are microwave devices made of compound semiconductor materials (GaAs, GaN etc)
- Temperature and voltage/electric field are the important stresses in the application of microwave devices
- In the space/defense environment many of the others are mitigated by the application environment.
- This presentation will focus on temperature activated degradation. The reliability metrics from the statistical formalism will be introduced and the procedures to obtain them will be detailed

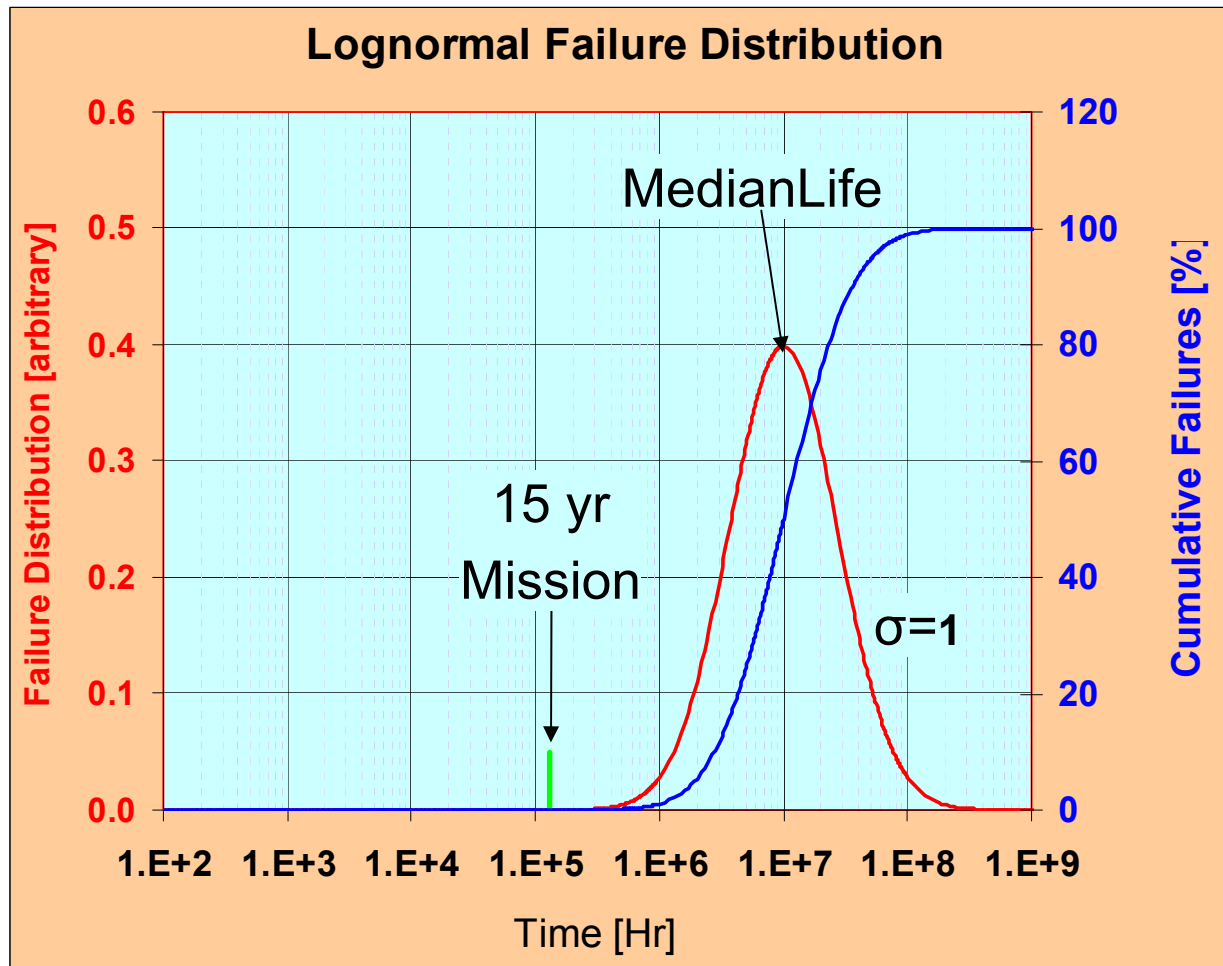
Main Theme: Thermally activated reliability metrics

Elements of the Statistical Formalism

- The Lognormal Lifetime Distribution
 - Failures are distributed ‘normally’ when plotted on log time scale
- The Cumulative Failure Fraction Plot
 - A linear plot can be taken as evidence for lognormal lifetime distribution
- The Arrhenius Reaction Rate Model - $t=t_0 \cdot e^{E_a/kT}$
 - The Arrhenius acceleration relationship is then
 - $ML_1/ML_2 = e^{E_a/kT_1}/e^{E_a/kT_2}$
- The Reliability Metrics from above are:
 - Median Life (ML) or MMTF
 - Sigma (σ) the dispersion – standard deviation of the log of lifetimes
 - Activation Energy

The Metrics: Median Life, Sigma and Activation Energy

The Lognormal Failures Distribution

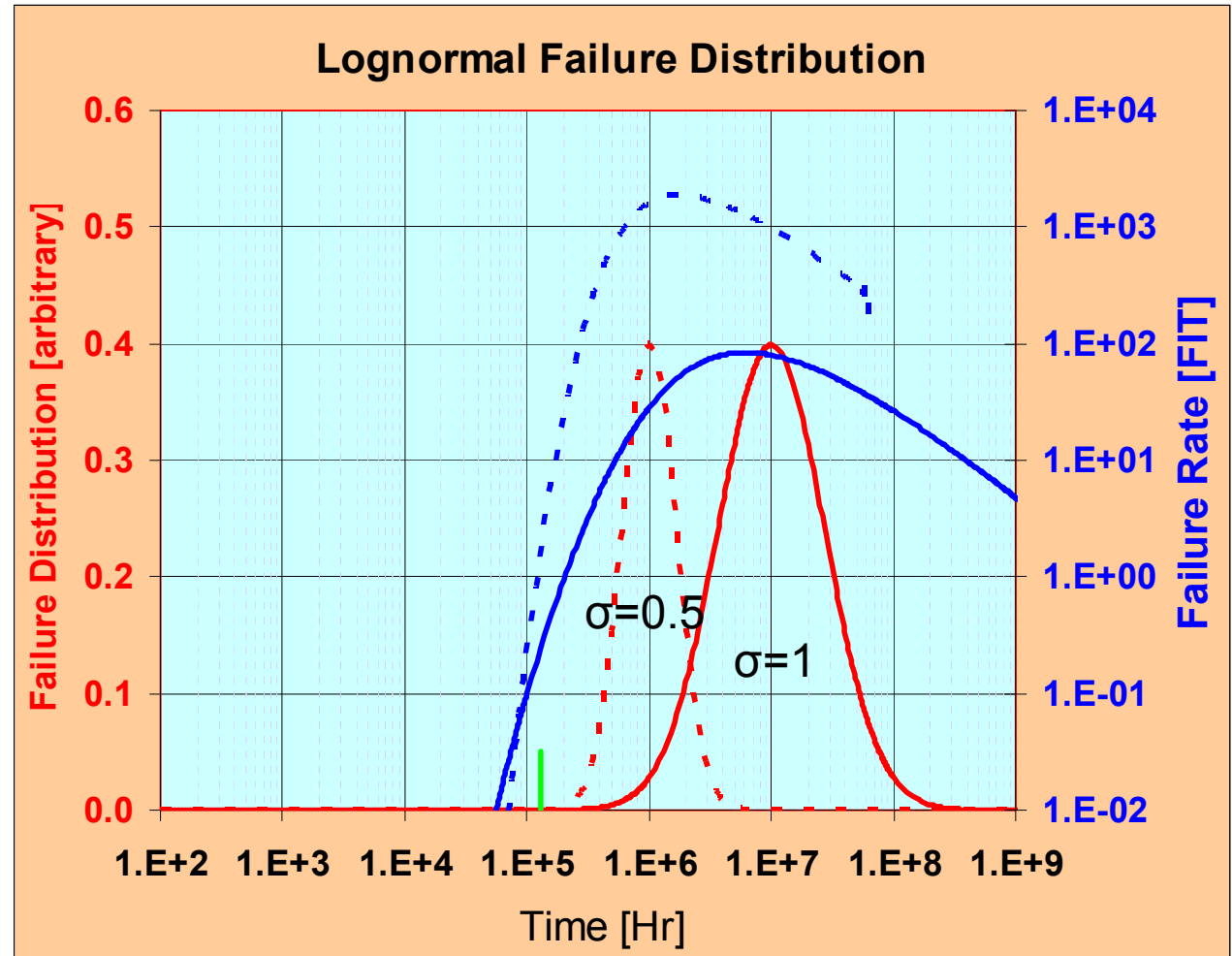


Distribution is 'normal' when plotted on log time scale

Trade Off Between ML and σ

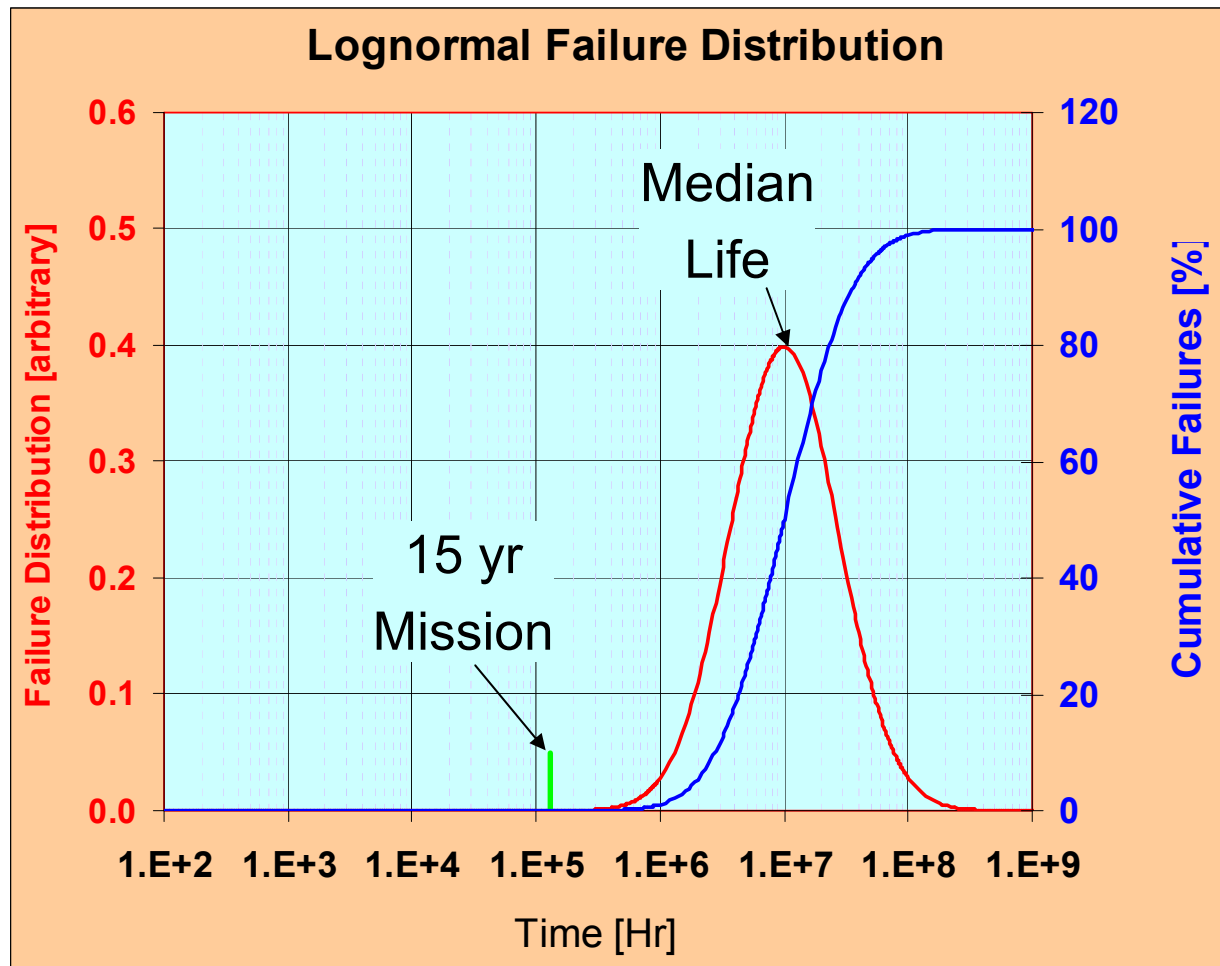
Failure Rate in FITs through mission time is negligible

FIT is a failure unit
And it is equivalent with 1 failure/ 10^9 hr



To maintain 'Same' Reliability at lower ML, σ has to be smaller

The Lognormal Failures Distribution



Note Margin Between Distribution Tail and Mission Time

The Cumulative Failure Fraction Plot

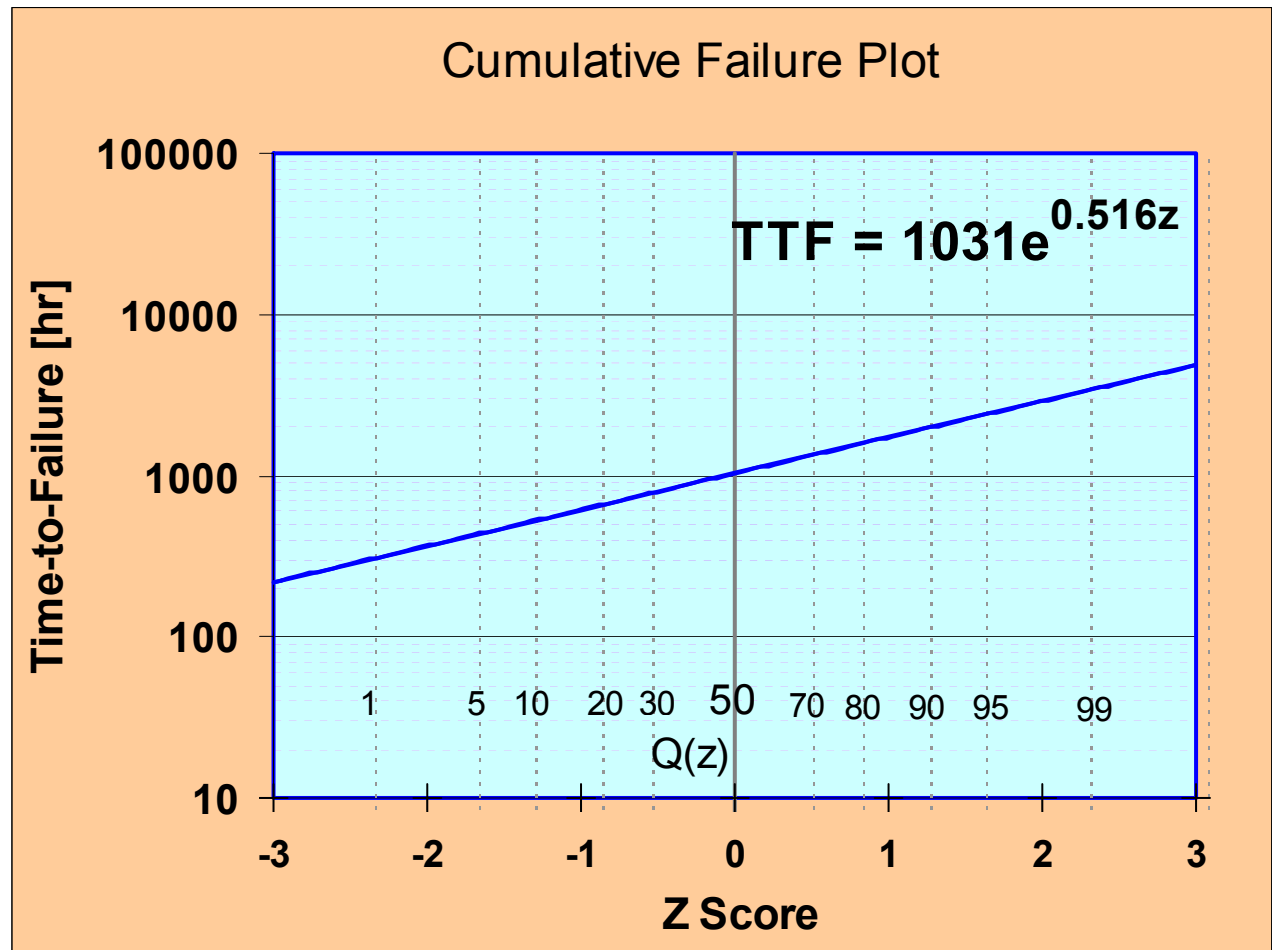
Note on the X scale both the Probability and Score scales are shown

The Plot is linear
 $\ln(\text{TTF}) = \sigma * z + \ln(\text{ML})$

The exponential curve fit in Excel returns the form

$$\text{TTF} = \text{ML} * e^{\sigma * z}$$

The extraction of ML and σ is direct



A linear plot is taken as evidence for lognormal lifetime distribution

The Arrhenius Reaction Rate Model

$$ML = C * e^{Ea/kT}$$

Or

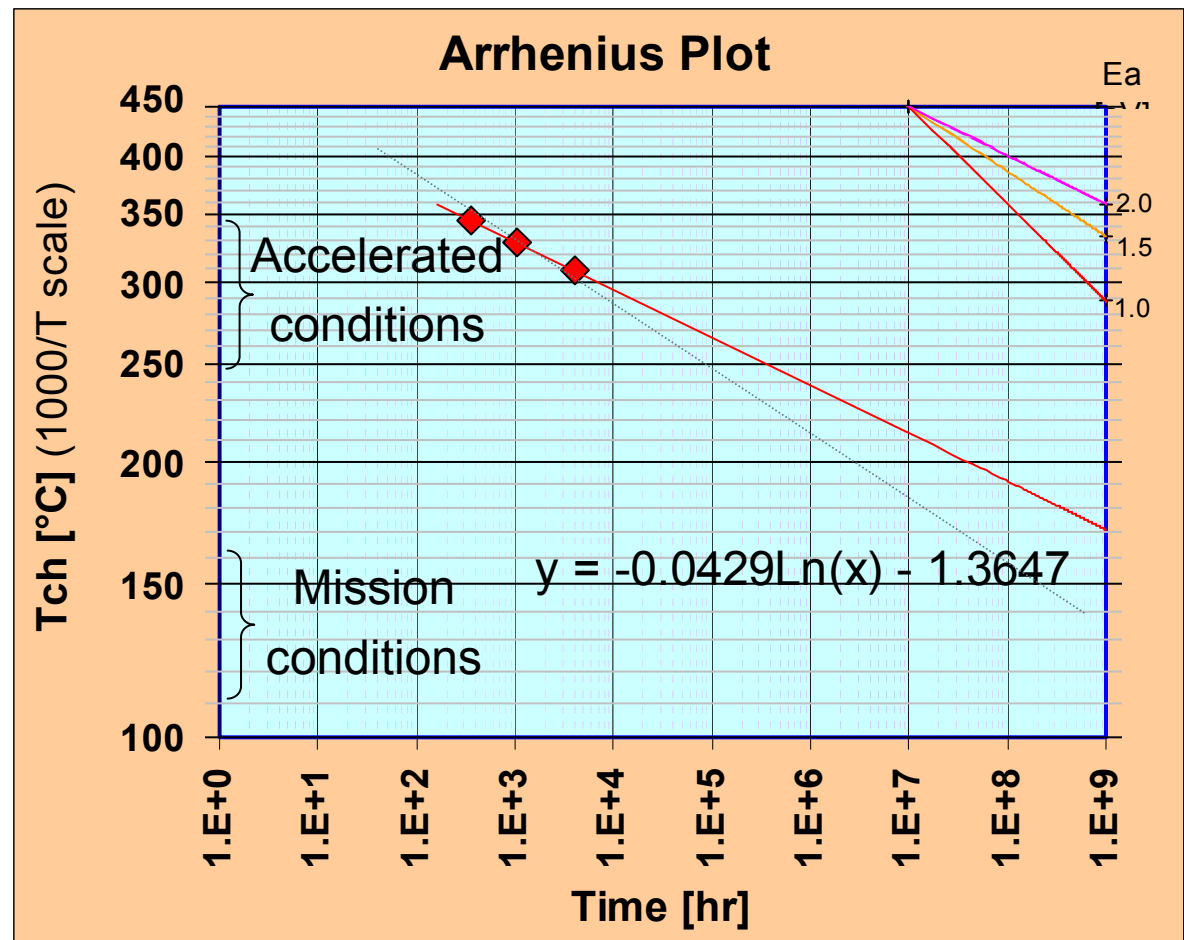
$$1000/T = A * \ln(ML) + C$$

The Plot is a straight line using these scales

The logarithmic curve fit in Excel returns this form and from the slope A the Activation Energy

$$Ea = 1000k/A = 0.0862/A$$

k is Boltzman's constant in eV*K⁻¹



The Ability to Thermally Accelerate Aging is Key to the Process

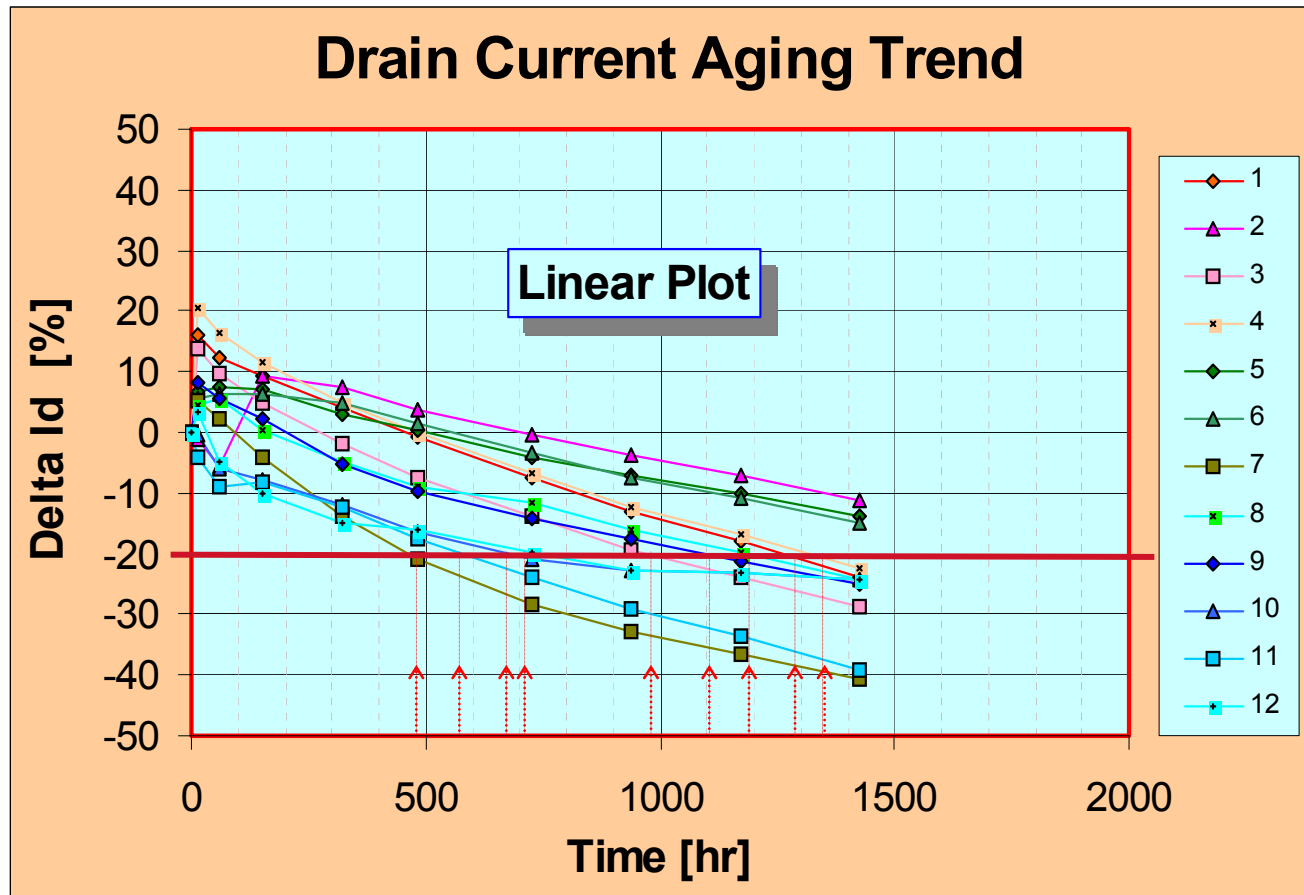
Life Test Scope

- Life Tests at minimum 3 temperatures are required to establish a credible trend
- T_{ch} for the Life Tests is determined from self heating due to DC operating power dissipation and base plate temperature setting
- Test Vehicles are 12 Schottky Gate Field Effect Transistors per temperature group
- 20% Decrease in Drain Current is the Failure Criterion
- Drain Current is a key performance parameter and it is correlated with RF Power output capability

FET Test Vehicles and -20% ΔI_d Failure Criterion

Life Test Data Analysis

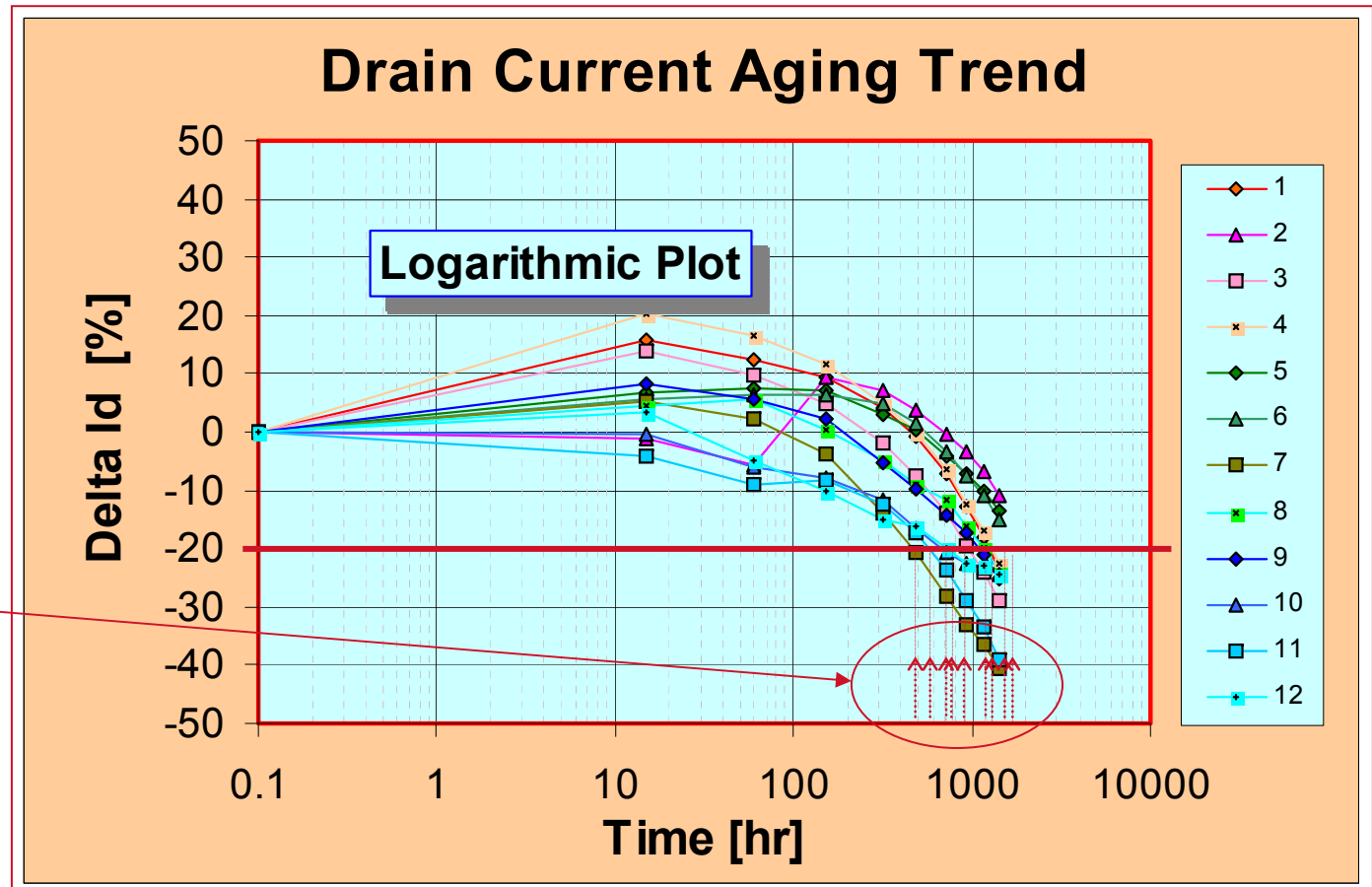
- Drain Current aging at $T_{ch}=329^{\circ}\text{C}$ - Linear trend plot



Times to Failure are indicated by arrows on the Time Scale

Life Test Data Analysis

- Drain Current aging at $T_{ch}=329^{\circ}\text{C}$ - Logarithmic trend plot



The Times-to-Fail are tabulated and ranked and used in the next step

Logarithmic trend plot is a better visual indicator of ML

Life Test Data Analysis

- The Time-to-Fail values are tabulated and ranked
- For each failure the cumulative failed fraction, Q, is calculated using the median ranking formula:

$$Q = (F - 0.3) / (N + 0.4)$$
 F is the number of failed parts; N is the number of parts in the test
- Q is converted to the z score using NORMSINV function in Excel

The resulting z-score and TTF data is plotted using the Cumulative Failure Fraction Plot

F cum # failures	Q [fraction] (F-0.3)/(N+0.4)	Z score	TTF [hr] sorted
1	0.05645	-1.58528	450
2	0.13710	-1.09346	570
3	0.21774	-0.77984	670
4	0.29839	-0.52904	700
5	0.37903	-0.30802	950
6	0.45968	-0.10125	1100
7	0.54032	0.101246	1174
8	0.62097	0.308024	1200
9	0.70161	0.529045	1200
10	0.78226	0.779842	1700
11	0.86290	1.093456	1900
12	0.94355	1.585278	2100

The Id trend plot is reduced to the TTF and Z-score data array

The Cumulative Failure Plot: T_{ch}=329°C

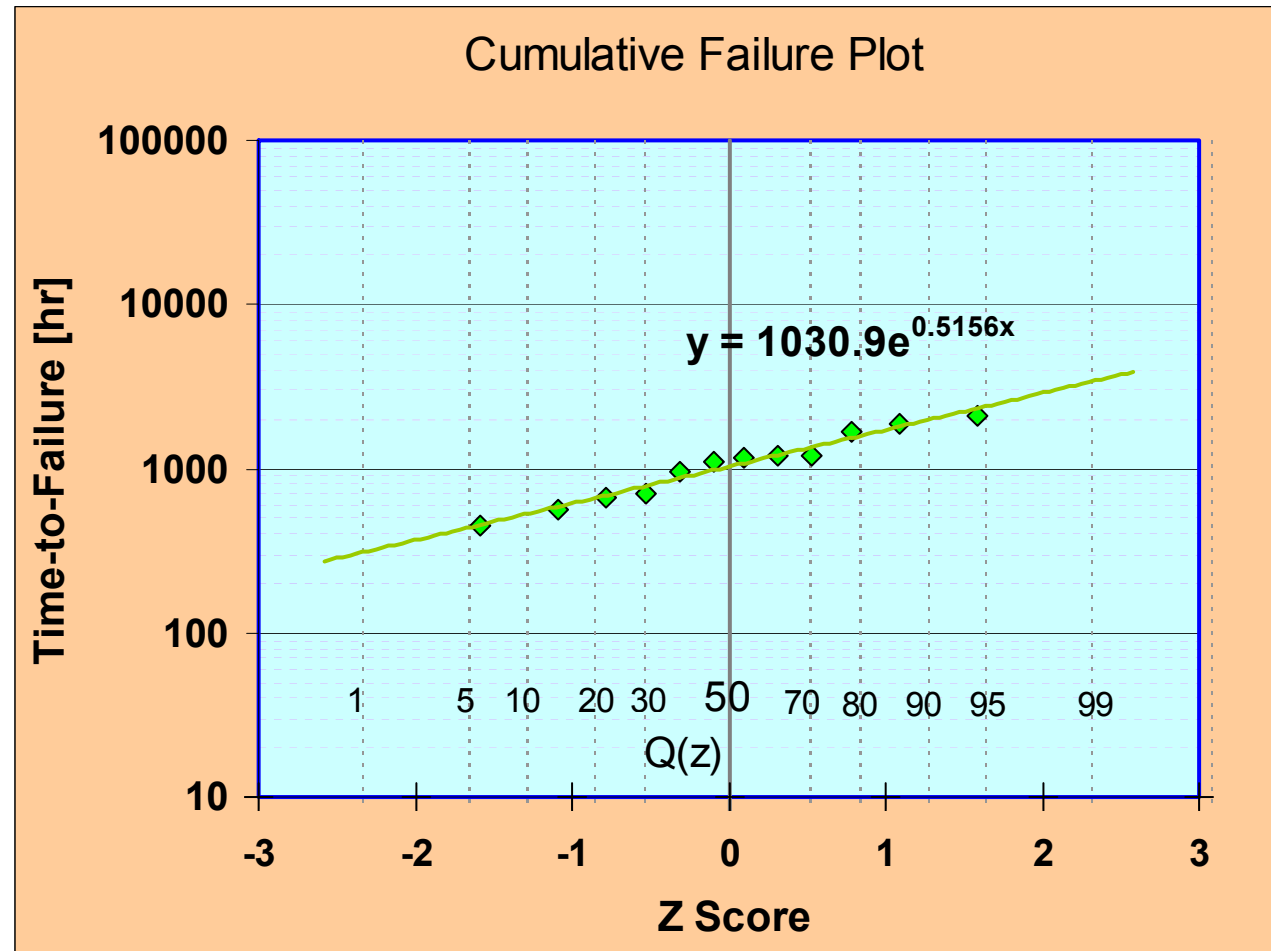
The exponential curve fit in Excel returns the form

$$TTF = ML * e^{\sigma * z}$$

The extraction of ML and σ is direct

$$ML = 1031 \text{ hr}$$

$$\sigma = 0.52$$



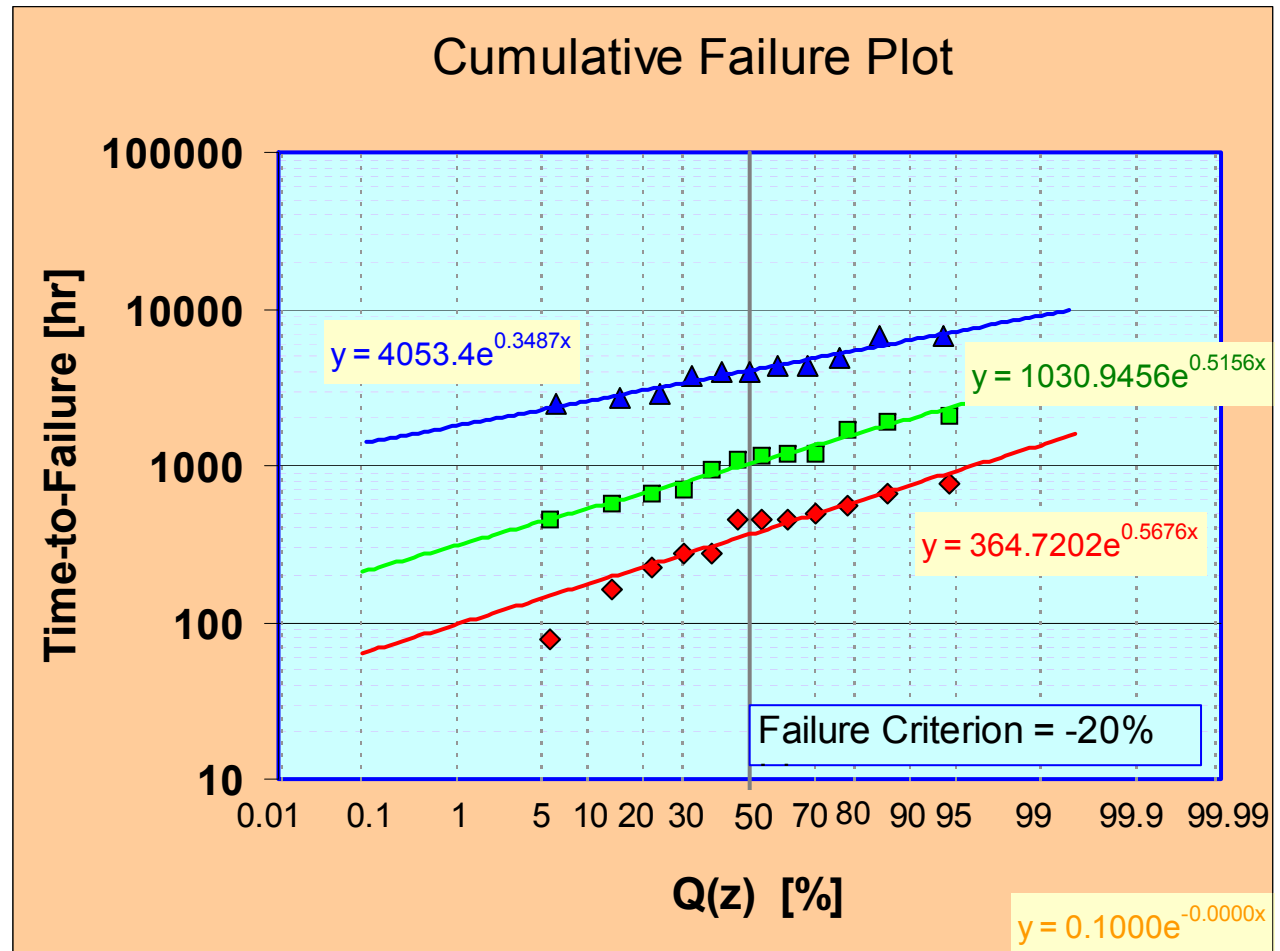
The Cumulative Failure Plot Provides ML and σ Directly

All 3 Cumulative Failure Plots

The extraction of ML and σ is direct for all 3 temperature groups

Tch[°C]	ML[hr]	σ
345	365	0.57
329	1031	0.52
308	4053	0.35

Tch and ML are ready to be plotted on the Arrhenius coordinates



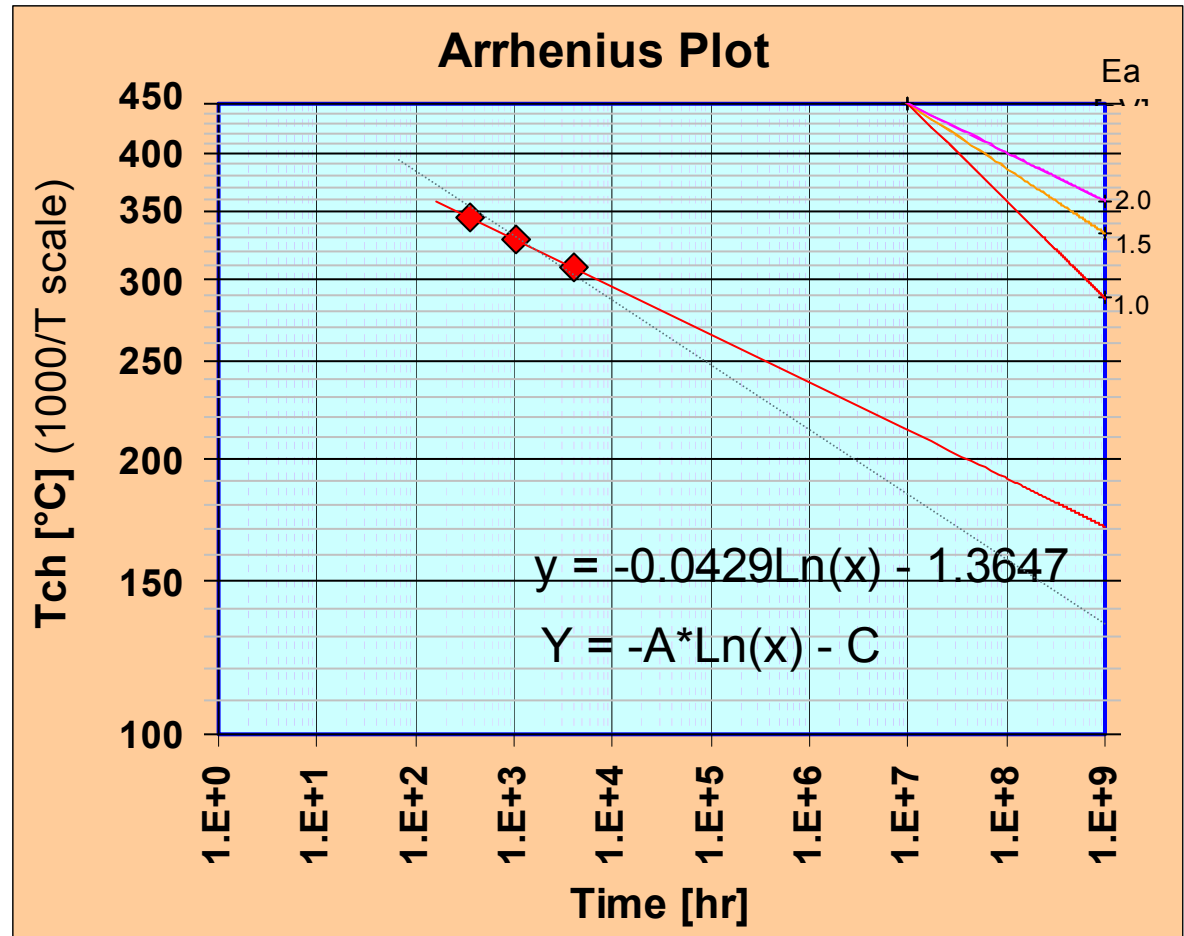
The Cumulative Failure Plot Provides ML and σ Directly

The Arrhenius Plot for the 3 Life Tests

- T_{ch} is converted to 1000/T_{ch} in [°K⁻¹]
- Note negative sign forces Temperature increase bottom to top

T _{ch} [°C]	ML [hr]	1000/T _{ch} [°K ⁻¹]
345	365	-1.618
329	1031	-1.661
308	4053	-1.721

- ML and 1000/T_{ch} are plotted on the Arrhenius Coordinates
- $E_a = 0.0862/A$
- $E_a = 2.01\text{eV}$



The Arrhenius Plot Provides E_a Directly

Reliability Metrics Summary

The Reliability Metrics based on all 3 temperature groups used in this example are

Tch[°C]	ML[hr]	σ	Ea[eV]
345	365	0.57	2.01
329	1031	0.52	
308	4053	0.35	

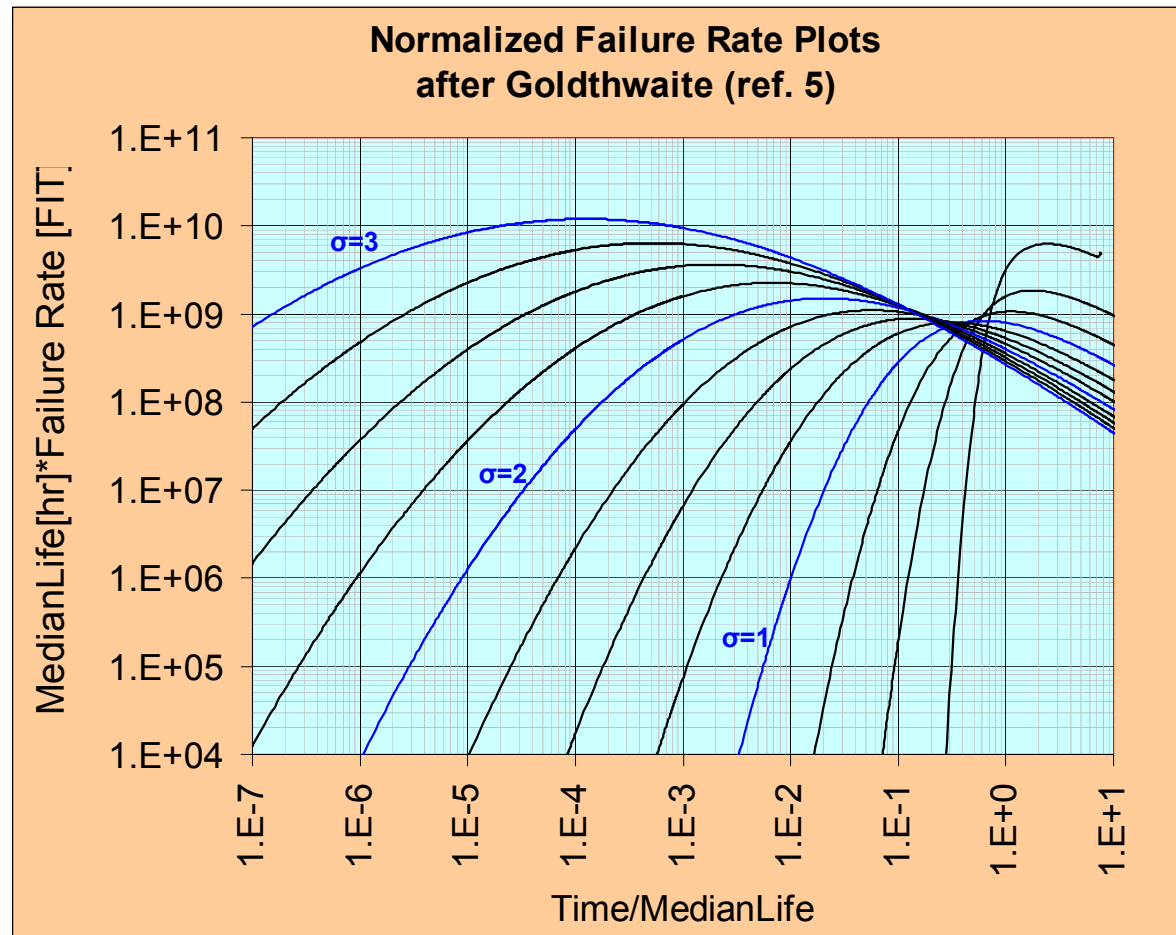
Projections are based on the Arrhenius relationship

$$ML1/ML2 = e^{Ea/kT1}/e^{Ea/kT2}$$

Extrapolate Time				
Ea (eV)	t1 [hr]	T1 [°C]	Unknown t2=?? [hr]	T2 [°C]
2.01	4.05E+03	308	1.313E+10	150
1.50	1.03E+03	329	2.116E+08	150

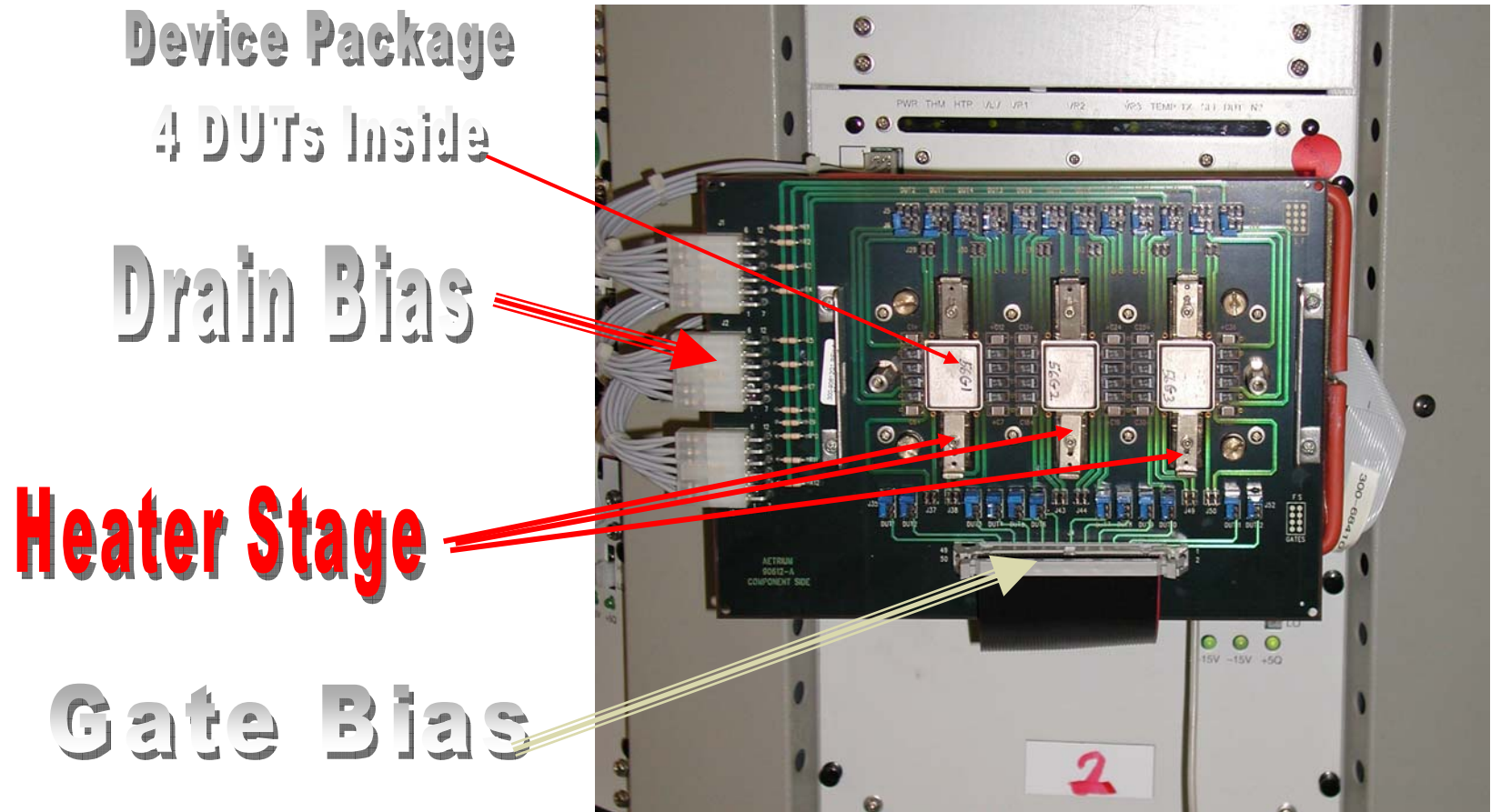
*The 2.01eV Arrhenius Line Projects ML= 1.3E10 at a Mission Tch=150°C
The Conservative 1.5eV Arrhenius Line Projects ML= 2.1E8 at Tch=150°C*

Reliability Metrics Summary



*Normalized Failure Rate Plot is Used to Validate
Our Extraction and Calculation Protocols*

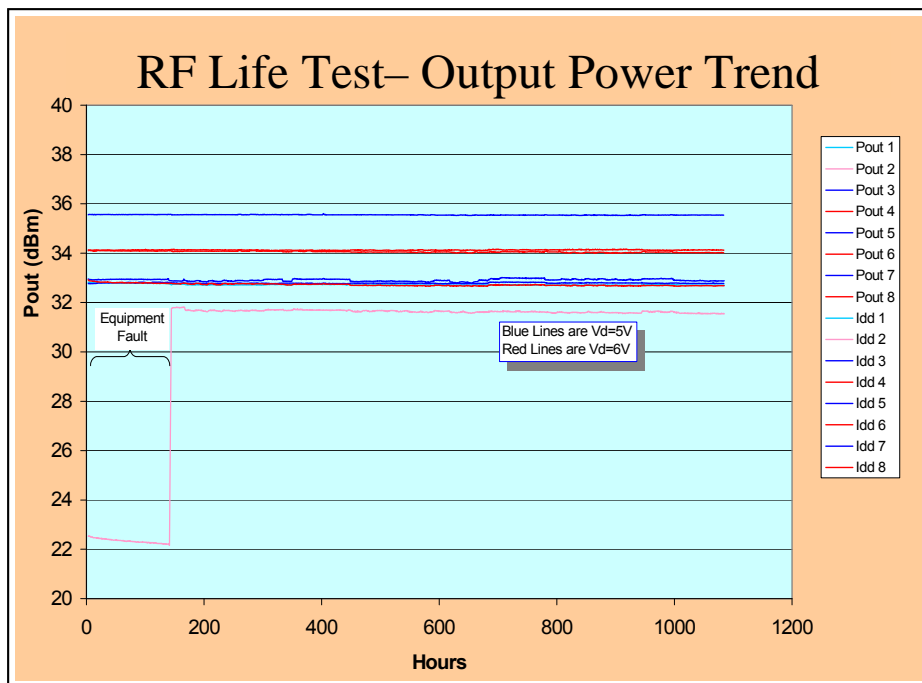
The Equipment/Set Up



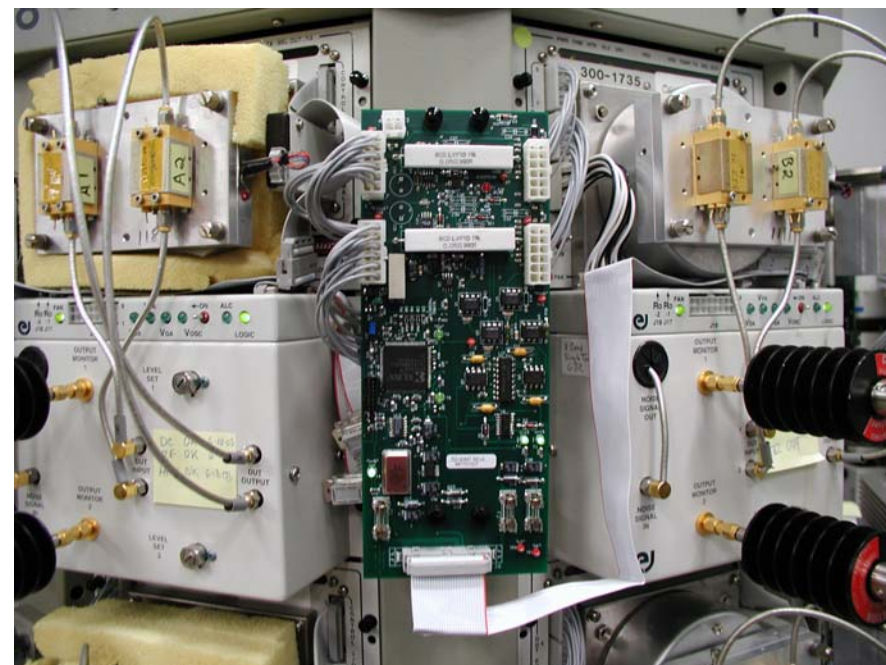
The Equipment Uses a Servo Feedback Loop Which Adjusts the Gate Voltage to Keep Constant Drain Current

The 2nd Key Stress in the application of microwave devices - Voltage/Electric field

RF Life Test Equipment



Stable Po during RF Life Test



RF Operational Life Tests Are Used to Mitigate High Field Effects Also Known as Hot Electron Effect

References

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4. W. B. Nelson, "Accelerated Testing Statistical Models, Test Plans, and Data Analysis", John Wiley & Sons, Inc, Copyright 1990, 2004
5. L. R. Goldthwaite, "Failure Rate Study for the Lognormal Lifetime Model", Proceedings of the 7th Symposium on Reliability and Quality Control, 1961 p. 208-213
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